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THW

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Stephen B. SIEGEL) Group Art Unit: 1762
Serial No: 10/789,020)
Filed: February 20, 2004) Primary Examiner: Marianne L. Padgett
For: UV Curing For Ink Jet Printers) Attorney Docket No: 6987/90555
) Confirmation No. 7154

SECOND SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Mail Stop: Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Dear Sir:

The patents, published patent applications, abstracts, and publications listed below were located during a prior patent search of the above-identified application or cited in a related U.S. Patent Application or an International Search Report or in an International Preliminary Report on Patentability of a corresponding or related International Patent Application. The patents, published patent applications, abstracts, and publications listed below generally relate to the subject matter of the invention, but do not fairly teach or suggest the claimed UV Curing For Ink Jet Printeres. Copies of the listed patents, published patent applications, abstracts, and publications, are enclosed for the consideration of the Primary Examiner.

1. Hochestein U.S. Patent Published Application No. US2001/0030866 A1 published October 18, 2001 pertains to an LED Integrated Heat Sink.

2. Sweatt et al. U.S. Patent Published Application No. US2002/0074554 A1 published June 20, 2002 pertains to a Microoptical System and Fabrication Method Therefor.

3. Cleary et al. U.S. Patent Published Application No. US2002/0149660 A1 published October 17, 2002 pertains to an Apparatus and Method For Setting Radiation-Curable Ink.

4. Kanie et al. U.S. Patent Published Application No. US2002/0175299 A1 published November 28, 2002 pertains to a Ultraviolet Irradiation Apparatus And Method Of Forming Cured Coating Film Using The Apparatus.

5. Ramler U.S. Patent No. 4,010,374 granted March 1, 1977 pertains to a Ultraviolet Light Processor And Method of Exposing Surfaces to Ultraviolet Light.

6. Le Creff U.S. Patent No. 4,990,971 granted February 5, 1991 pertains to a Light Emitting Diode Network.

7. Ignatius et al. U.S. Patent No. 5,278,432 granted January 11, 1994 pertains to an Apparatus For Providing Radiant Energy.

8. Kennedy U.S. Patent No. 5,420,768 granted May 30, 1995 pertains to a Portable LED Photocuring Device.

9. D'Silva U.S. Patent No. 5,762,867 granted June 9, 1998 pertains to an Apparatus And Method For Activating Photoactive Agents.

10. Masuda et al. U.S. Patent No. 6,188,086 B1 granted February 13, 2001 pertains to a Light Emitting Diode Array And Optical Image Forming Apparatus With Light Emitting Diode Array.

11. Cleary et al. U.S. Patent No. 6,457,823 B1 granted October 1, 2002 pertains to an Apparatus And Method For Setting Radiation-Curable Ink.

12. Vackier et al. U.S. Patent No. 6,525,752 B2 granted February 25, 2003 pertains to an Exposure Unit With Staggered LED Arrays.

13. Kramer U.S. Patent No. 6,630,286 B2 granted October 7, 2003 pertains to a Process for Preparing a Printing Plate.

14. Jin et al. U.S. Patent No. 6,783,810 B2 granted August 31, 2004 pertains to Reducing Polymerization Stress By Controlled Segmental Curing.

15. Abstract: Noburuu et al. Japanese Patent Publication Application No. JP 2000-268416 published September 29, 2000 of Global Mach KK pertains to an Optical Disk Adhering Apparatus.

16. Abstract: Eiji et al. Japanese Patent Publication Application No. JP 2001-209980 published August 3, 2001 of Matsushita Electric Ind. Co. Ltd. pertains to a Method and Device For Production of Optical Information Recording Medium.

17. Abstract: Shigeru et al. Japanese Patent Publication Application No. JP 2005-129662 published May 19, 2005 of Iwasaki Electric, Co. Ltd. pertains to Manufacture of Light Emission Diode Lamp.

18. Publication: "*Photoinitiators for UV Curing Key Products Selection Guide, Coating Effects*", by Ciba Specialty Chemicals, Edition 2001, Switzerland.

19. Publication: "*Photoinitiators for UV Curing Formulators' Guide for Coatings, Additives*", by Ciba Specialty Chemicals, Edition 2001, Switzerland.

20. Publication: "*Optical Properties of Si-Doped $Al_xGa_{1-x}N/Al_yGa_{1-y}N$ ($x=0.24-0.53$, $y=0.11$) Multi-Quantum-Well Structures*" by H. HIRAYAMA and Y. AOYAGI, The Institute of Physical and Chemical Research, Saitama, Japan, MRS Internet J. Nitride Semicond. Res. 4S1,G3.74 (1999).

Authorization is hereby given to charge any fees in connection with this Second Supplemental Information Disclosure Statement or any deficiency in fees or any other fees in connection with the subject application to our Deposit Account No. 23-0920.

Dated: February 2, 2006

Respectfully submitted,

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Attorney Docket No. 6987/90555
Serial No. 10/789,020

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10/24/2001 W&K Substitutes for Form PTO-SB/08A, which is a USPTO Substitute for form 1449A/PTO and 1449B/PTO				Complete if Known	
				Application Number	10/789,020
				Filing Date	February 20, 2004
				First Named Inventor	Stephen B. Siegel
				Group Art Unit	1762
				Primary Examiner Name	Marianne L. Padgett
				Confirmation No.	7154
				Attorney Docket Number	6987/90555
Sheet	1	of	1		

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.¹	Document Number Number - Kind Code² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	1	US2001/0030866A1	10-18-2001	Hochestein	
	2	US2002/0074554A1	06-20-2002	Sweatt et al.	
	3	US2002/0149660A1	10-17-2002	Cleary et al.	
	4	US2002/0175299A1	11-28-2002	Kanie et al.	
	5	4,010,374	03-01-1977	Ramler	
	6	4,990,971	02-05-1991	Le Creff	
	7	5,278,432	01-11-1994	Ignatius et al.	
	8	5,420,768	05-30-1995	Kennedy	
	9	5,762,867	06-09-1998	D'Silva	
	10	6,188,086 B1	02-13-2001	Masuda et al.	
	11	6,457,823 B1	10-01-2002	Cleary et al.	
	12	6,525,752 B2	02-25-2003	Vackier et al.	
	13	6,630,286 B2	10-07-2003	Kramer	
	14	6,783,810 B2	08-31-2004	Jin et al.	
FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No.¹	Foreign Patent Document Country Code³-Number⁴-Kind Code⁵ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	15	Japanese Patent Publication Application No. JP 2000-268416 B	09-29-2000	Global Mach KK	
	16	Japanese Patent Publication Application No. JP 2001-209980 B	08-03-2001	Matsushita Electric Ind. Co. Ltd.	
	17	Japanese Patent Publication Application No. JP 2005-129662 B	05-19-2005	Iwasaki Electric Co. Ltd.	
OTHER ART - NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No.¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			T⁶
	18	Publication: "Photoinitiators for UV Curing Key Products Selection Guide, Coating Effects", by Ciba Specialty Chemicals, Edition 2001, Switzerland.			✓
	19	Publication: "Photoinitiators for UV Curing Formulators' Guide for Coatings, Additives", by Ciba Specialty Chemicals, Edition 2001, Switzerland.			✓
	20	Publication: "Optical Properties of Si-Doped Al _x Ga _{1-x} N/Al _y Ga _{1-y} N (x=0.24-0.53, y=0.11) Multi- Quantum-Well Structures" by H. Hirayama and Y. Aoyagi, The Institute of Physical and Chemical Research, Saitama, Japan, MRS Internet J. Nitride Semicond. Res. 4S1, G3.74 (1999).			✓

Examiner Signature	Date Considered
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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